

SIMULATION OF QUASILINEAR PARABOLIC EQUATIONS BY NETWORKS OF FIELD-EFFECT TRANSISTORS

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The possibility of using networks of field-effect transistors to simulate processes described by quasilinear parabolic equations is considered. Simulation results are compared with the data of a numerical calculation.

The use of R- and RC-networks to simulate processes described by the quasilinear parabolic equation

$$\frac{\partial}{\partial x} \left[A \frac{\partial T}{\partial x} \right] - B \frac{\partial T}{\partial t} = 0, \quad 0 \leq x \leq l, \quad t \geq t_0, \quad (1)$$

gives rise to a number of difficulties, not yet completely overcome, connected with the need to realize the prescribed functional relationships $A = A(T)$, $B = B(T)$ [1, 2]. For certain commonly occurring forms of $A(T)$ and $B(T)$ this problem can be solved by using RC-networks in which the nonlinear active resistances are various types of field-effect transistors (FET's).

Consider for simplicity the case when the coefficient B does not depend on T (i.e., $B = B_0 = \text{const}$). [The case when B depends on T is readily reduced to the constant- B case by means of the substitution $T^* = \int B(T) dT$.] By dividing the segment $[0, l]$ into n equal parts and replacing the spatial derivatives by finite-difference relationships, we arrive at a set of ordinary differential equations of the following type [3]:

$$\frac{n^2}{l^2} \left[\int_{T_{i+1}}^{T_i} A(T) dT - \int_{T_i}^{T_{i-1}} A(T) dT \right] = -B_0 \frac{dT_i}{dt}, \quad i = 1, 2, \dots, n-1. \quad (2)$$

We introduce generalized dimensionless variables \bar{A} , \bar{T} , \bar{l} , \bar{t} by means of the relationships

$$A(T) = A_0 \bar{A}(\bar{T}), \quad T = T_0 \bar{T}, \quad l = l_0 \bar{l}, \quad t = t_0 \bar{t}. \quad (3)$$

As a result we obtain

$$\left[\int_{\bar{T}_{i+1}}^{\bar{T}_i} \bar{A}(\bar{T}) d\bar{T} - \int_{\bar{T}_i}^{\bar{T}_{i-1}} \bar{A}(\bar{T}) d\bar{T} \right] = - \frac{B_0 l_0^2 \bar{l}^2}{A_0 n^2 t_0} \cdot \frac{d\bar{T}_i}{d\bar{t}}, \quad i = 1, 2, \dots, n-1. \quad (4)$$

To simulate (4) we utilize the network shown in Fig. 1. The following condition holds at each node of the network:

$$I_{i+1} - I_i = -C_0 \frac{dV_i}{d\tau}. \quad (5)$$

We transform to dimensionless variables \bar{I}_i , \bar{V}_i , $\bar{\tau}$ by means of the relationships

$$I_i = I_0 \bar{I}_i, \quad V_i = V_0 \bar{V}_i, \quad \tau = \tau_0 \bar{\tau}, \quad (6)$$

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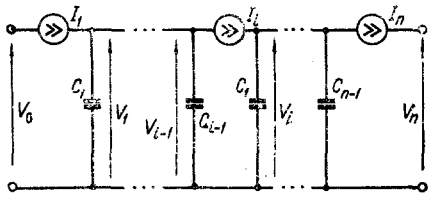


Fig. 1

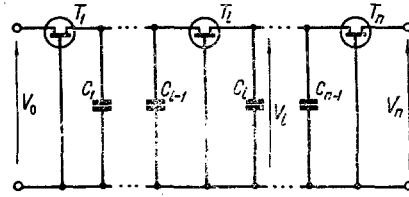


Fig. 2

Fig. 1. Electrical model of medium with nonlinear transport parameters.

Fig. 2. Network using FET's for simulation of processes described by Eq. (1).

$$\bar{I}_{i+1} - \bar{I}_i = - \frac{C_0 V_0}{I_0 \tau_0} \cdot \frac{d\bar{V}_i}{dt} \quad (7)$$

On comparing (4) and (7) we find

$$\frac{l^2}{n^2} \cdot \frac{B_0}{A_0 t_0} = \frac{C_0 V_0}{I_0 \tau_0} \quad (8)$$

$$I_i = \frac{I_0}{V_0} \int_{V_i}^{V_{i-1}} \bar{A} \left(\frac{T_0}{V_0} V \right) dV \quad (9)$$

Expression (9) coincides with the expression describing the steep part of the volt-ampere characteristic of the field-effect transistor, for which the dependence of the running resistance of the channel $R(V)$ on the channel-gate voltage V is given by

$$R(V) = \frac{V_0}{I_0 L_C \bar{A} \left(\frac{T_0}{V_0} V \right)} \quad (10)$$

where L_C is the channel length, and voltages V_{i-1} and V_i play, respectively, the roles of the source-gate and drain-gate voltage.

For transistors with a controlling p-n junction and for insulated-gate FET's the functions $R(V)$ have the following form [4]:

$$R(V) = \frac{1}{\sigma z a} \left[\frac{1}{1 - \sqrt{\frac{V}{V_p}}} \right] \quad (11)$$

$$R(V) = \frac{L_C}{\mu C_t (V - V_p)} \quad (12)$$

Replacing in Fig. 1 current sources of FET's of the appropriate type, we obtain a network for the simulation of processes for which the functional dependence $A(T)$ is approximated by expressions (10), (11) or (10), (12).

By way of example, consider the temperature distribution in a single-layer diatomic wall of thickness 0.2 m under the following boundary conditions:

$$T(x, 0) = 0^\circ C, \quad T(0, t) = T_{in} = 600^\circ C, \quad \left. \frac{\partial T(x, t)}{\partial x} \right|_{x=l} = 0 \quad (13)$$

The temperature dependence of the thermal conductivity is given by the expression $\lambda = 0.116 + 0.00018T$ W/m·deg; the specific heat $c = 1.05 \cdot 10^3$ J/kg·deg; and the density $\gamma = 560$ kg/m³ [5].

The simulation was carried out using a network (Fig. 2) comprising 10 KP301 metal-dielectric FET's selected so that the spread in the slopes and pinch-off voltages did not exceed 4%. The effect of the stray capacitance of the transistors on the duration of the transient process was eliminated by choosing C_0 equal to 220 pF, i.e., much greater than the transistor interelectrode capacitances. In Fig. 3 the results of the measurements (the circles) are compared with the results of a numerical solution (solid curves). The deviation between the results of simulation and numerical calculation lies within the limits of measurement error and

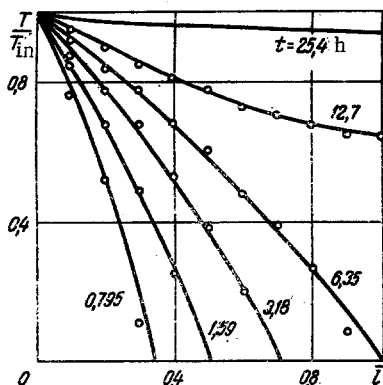


Fig. 3. Temperature distribution in single-layer wall.

does not exceed 6%. By an analogous approach the method described above can be used for the simulation of a wide range of problems in heat and mass transport.

NOTATION

t , time; T , temperature; T_{in} , initial temperature; x , coordinate; L_C , z , a , σ , length, width, thickness, and conductivity of channel, respectively; μ , mobility of charge carriers; C_t , total gate-channel capacitance; V_p , pinch-off voltage for insulated gate (controlling p-n junction) transistor; I , current; V , voltage; C_o , capacitance; λ , thermal conductivity; c , specific heat; γ , density; \bar{I} , \bar{V} , $\bar{\tau}$, \bar{A} , \bar{T} , \bar{z} , \bar{t} , dimensionless variables; I_o , V_o , τ_o , A_o , T_o , z_o , t_o , constant coefficients.

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